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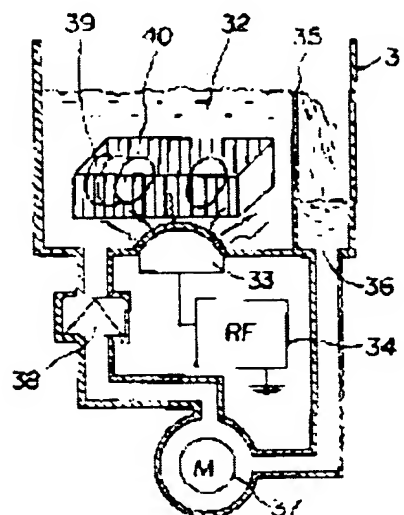
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(54) CLEANING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To properly remove contaminants on a semiconductor substrate.

SOLUTION: The surface of a semiconductor substrate is cleaned by blowing liquid nitrogen against the substrate.



31 : 槽
32 : 液体窒素
33 : 超音波振動子
39 : 半導体基板

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